

**Supporting Information**

**Insight into the PEC and Interfacial Charge Transfer Kinetics at the  
Mo Doped BiVO<sub>4</sub> Photoanodes**

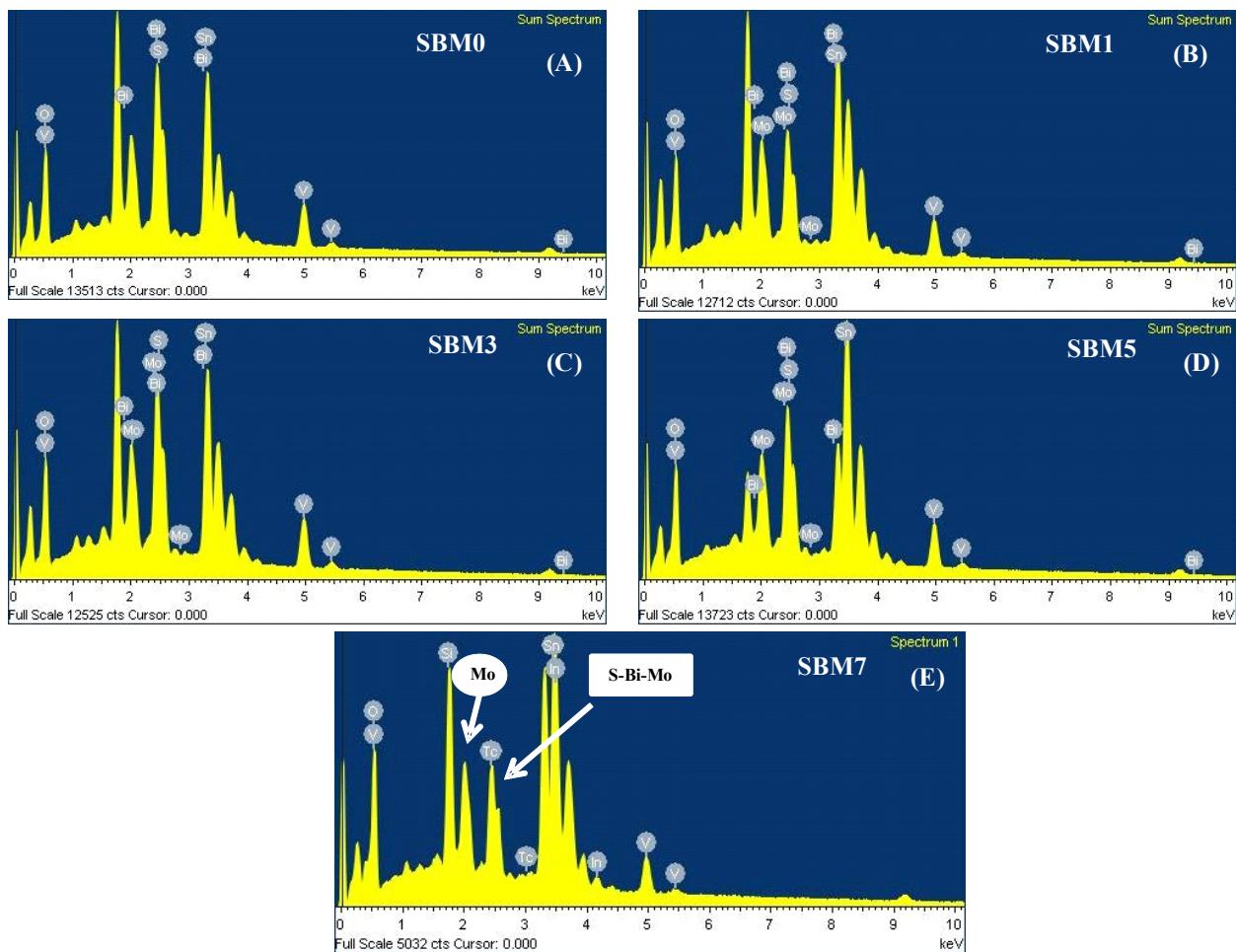
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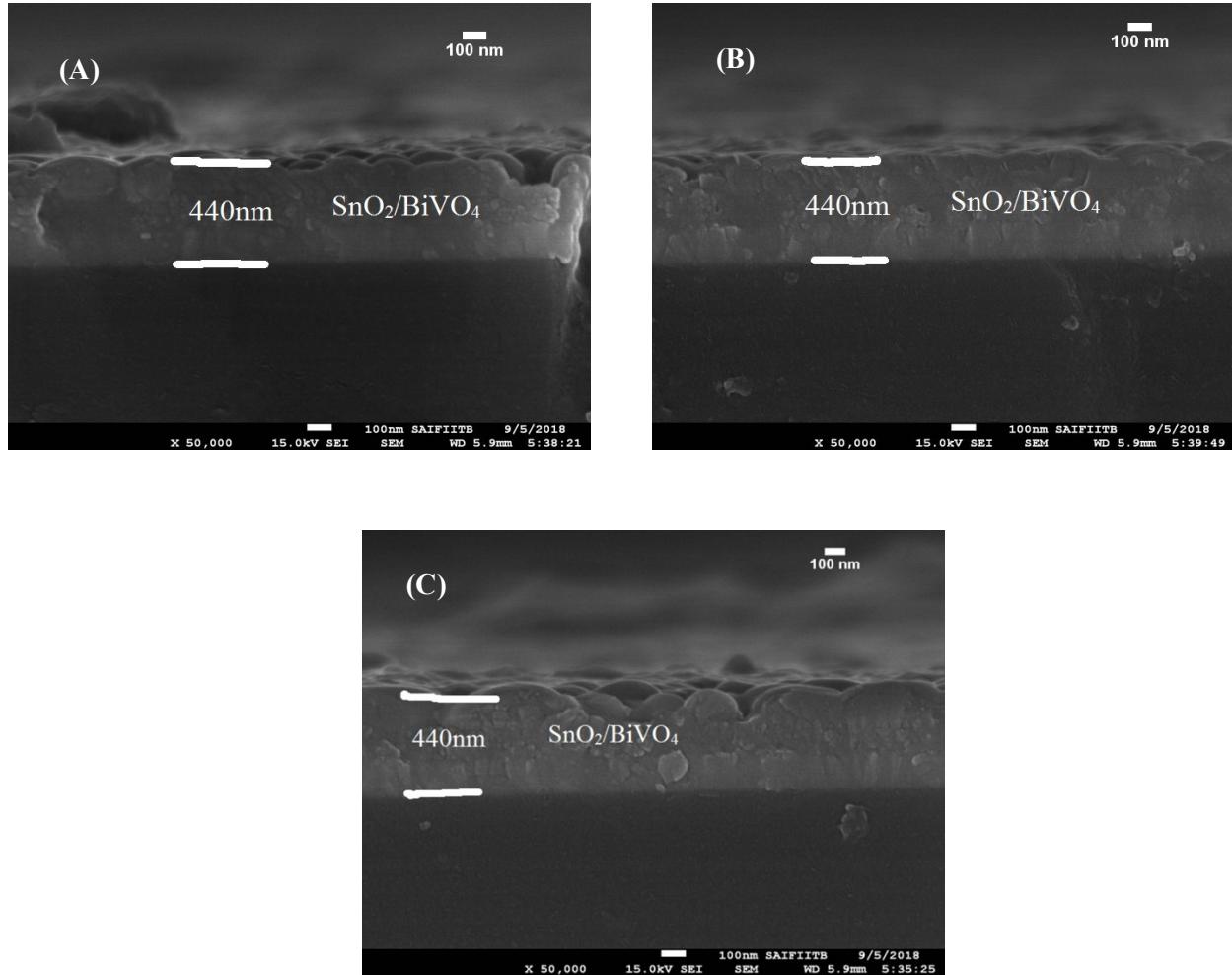


**Fig. S1.** EDS analysis of different catalysts for calculation of Bi, V, O and Mo in the photoanodes (A) SBM0, (B) SBM1, (C) SBM3, (D) SBM5 and (E) SBM7.

**Table S1.** Elemental analysis of Bi, V, O, Mo and Sn in  $\text{BiVO}_4$  photoanodes.

Elements	SBM0	SBM1	SBM3	SBM5	SBM7
	Atomic %				
<b>Bi M</b>	11.20	10.51	11.14	11.34	10.47
<b>V K</b>	11.45	9.54	9.24	8.39	7.34

<b>O K</b>	72.06	71.31	69.63	64.49	66.02
<b>Mo L</b>	-	0.78	3.18	4.43	6.37
<b>Sn L</b>	5.10	6.53	5.57	5.90	9.80



**Fig. S2.** Cross-sectional view of photoanodes for thickness measurements (A) SBM0, (B) SBM3 and (C) SBM7. Total thickness of film is 440nm

Table S2. The comparative study of the performance of BiVO<sub>4</sub> based photoanodes.

Photoanodes	j at 1.23 V vs. RHE (mAcm <sup>-2</sup> ) without co- catalyst	j at 1.23 V vs. RHE (mAcm <sup>-2</sup> ) With co- catalyst	Buffer/pH	Year	Reference
Mo:BiVO <sub>4</sub>	2.16	na	Natural sea water, pH = 6	2011	Luo et al. <sup>1</sup>
Mo:BiVO <sub>4</sub> /CoPi	0.2	1.0	0.5 M Na <sub>2</sub> SO <sub>4</sub> , pH = 7	2011	Pilli et al. <sup>2</sup>
W:BiVO <sub>4</sub> /CoPi	1.1	3	0.1 M PBS, pH = 7.3	2013	Abdi et al. <sup>3</sup>
BiVO <sub>4</sub> /FeOOH/ NiOOH	1.9	4.5	0.5 M PBS, pH = 7	2014	Kim et al. <sup>4</sup>
Mo:BiVO <sub>4</sub> /FeO OH	1.1	3.0	0.1 M PBS, pH = 7	2014	Park et al. <sup>5</sup>
H <sub>2</sub> treated Mo:BiVO <sub>4</sub> /CoPi	2.5	4.9	0.1 M PBS, pH = 7	2015	Kim et al. <sup>6</sup>
N <sub>2</sub> treated BiVO <sub>4</sub> /FeOOH	2.90	5.20	0.5 M PBS, pH = 7.2	2015	Kim et al. <sup>7</sup>
BiVO <sub>4</sub> /CoO <sub>x</sub> /Ni O	1.1	3.5	0.1 M PBS, pH = 7	2015	Zhong et al. <sup>8</sup>
Mo:BiVO <sub>4</sub>	1.9	na	0.1M PBS, pH = 7.3	2017	Rohloff et al. <sup>9</sup>
ZnO/BiVO <sub>4</sub> /CoP i	0.28	2.45	0.3 M Na <sub>2</sub> SO <sub>4</sub> , pH = 7.5	2017	Yang et al. <sup>10</sup>
Mo:BiVO <sub>4</sub>	2.1	na	0.1 M Na <sub>2</sub> SO <sub>3</sub>	2018	Huang et al. <sup>11</sup>

$\text{SnO}_2/\text{BiVO}_4$	2.62	na	0.5 M PBS, pH = 7.	2018	Byun et al. <sup>12</sup>
Fluorinated $\text{Mo:BiVO}_4/\text{CoPi}$	1.45	5.43	0.1 M PBS, pH = 7.2	2019	Rohloff et al. <sup>13</sup>
$\text{BiVO}_4/\text{Fe-phenolic layer (FTA)}$	1.5	5.50	0.5 M BBS, pH = 9	2020	Cao et al. <sup>14</sup>
$\text{Mo:BiVO}_4$	1.50 3.46 (in 0.1 M $\text{Na}_2\text{SO}_3$ )	na	0.1 M PBS, pH = 7		<b>This work</b>

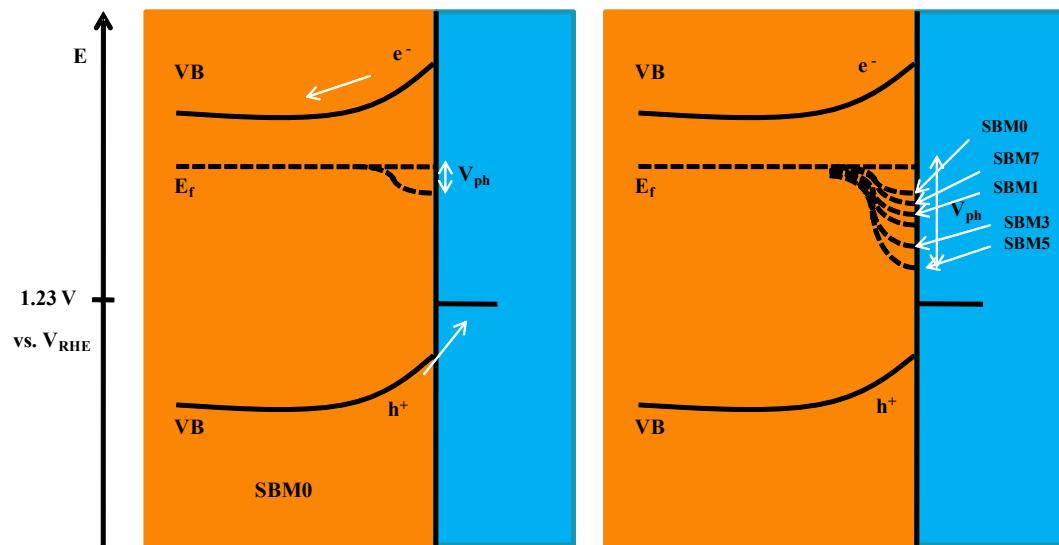
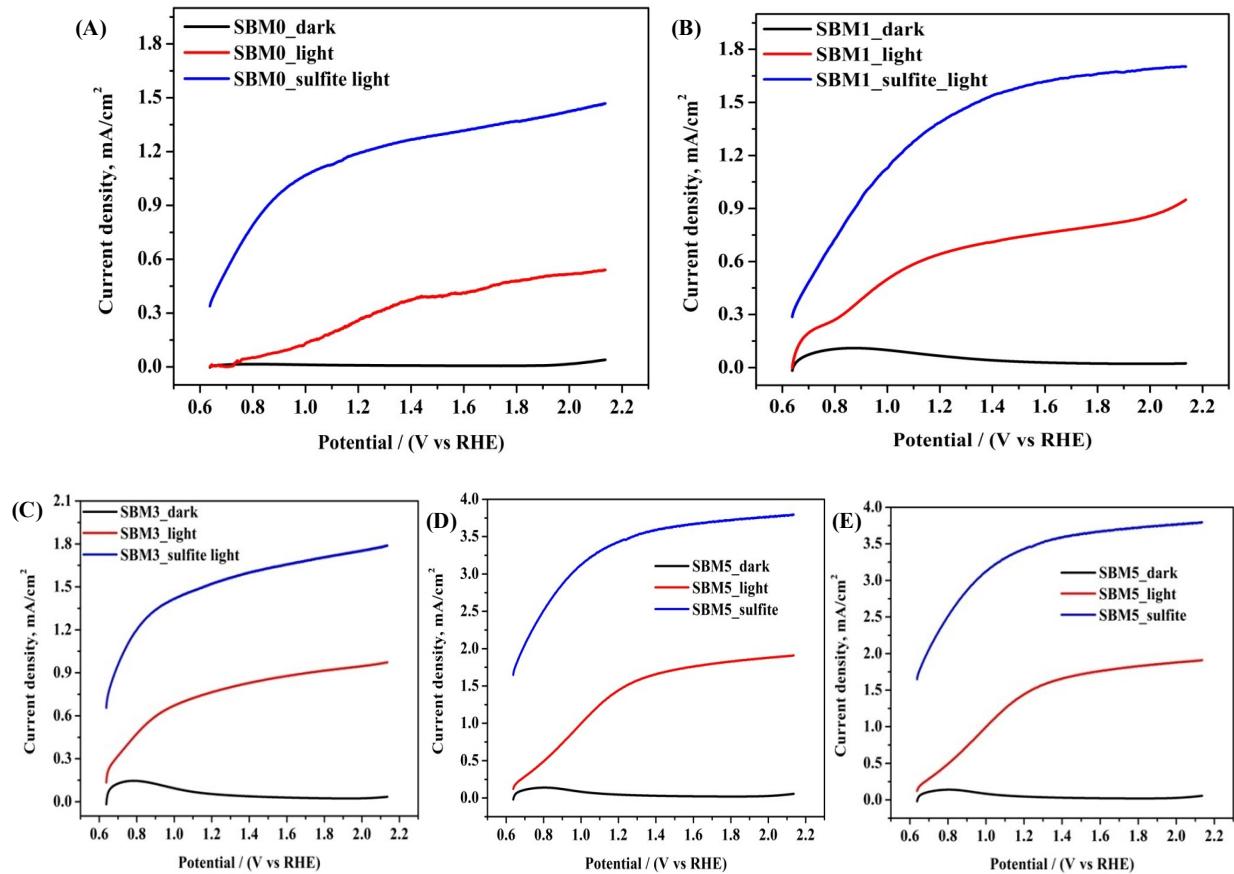
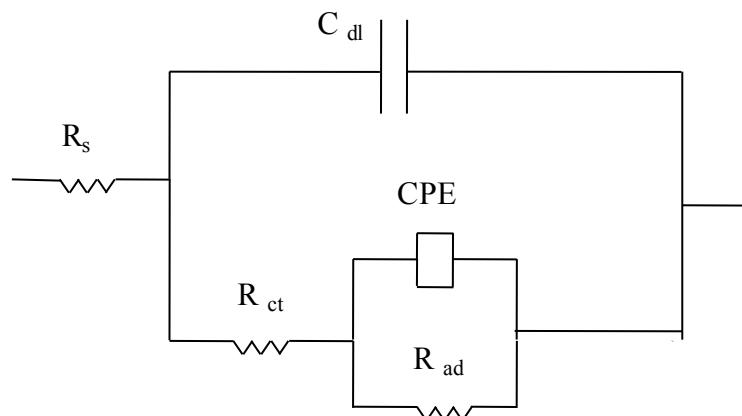


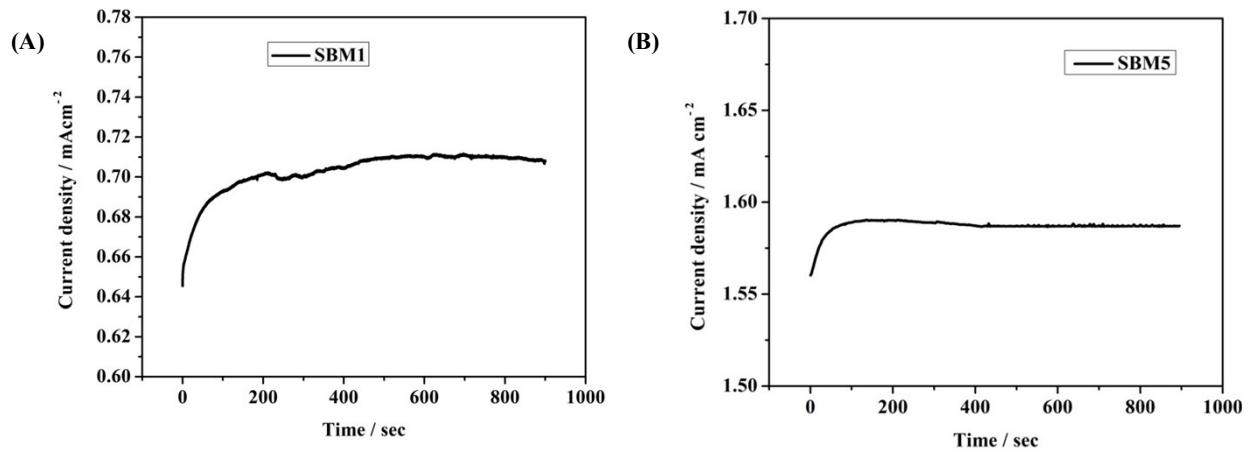
Fig. S3. Band diagram of  $\text{BiVO}_4$  and Mo doped  $\text{BiVO}_4$ . The band diagram is constructed using UV-vis spectroscopy, OCPV and flat band potential measurements (not to scale).



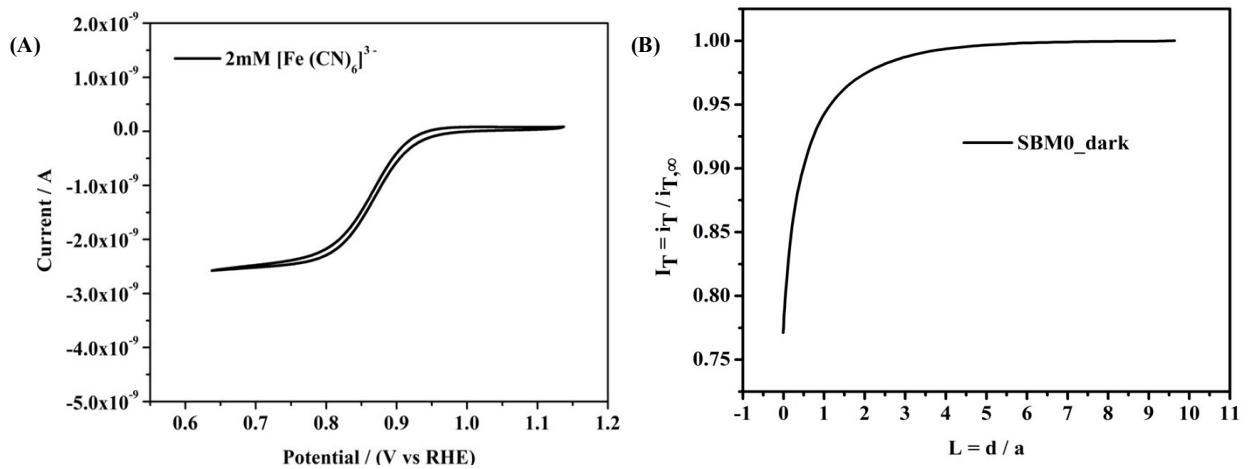
**Fig. S4.** LSV of photoanodes (A) SBM0, (B) SBM1, (C) SBM3, (D) SBM5 and (E) SBM7 in 0.5M  $\text{Na}_2\text{SO}_4$  in 0.1M PBS for PEC water oxidation reaction and 0.1M  $\text{Na}_2\text{SO}_3$  as hole scavenger for charge transfer kinetics measurement.



**Fig. S5.** The equivalent electrical circuit used for fitting the impedance spectroscopy data.



**Fig. S6.** Stability test of (A) SBM1 and (B) SBM5 in 0.5M  $\text{Na}_2\text{SO}_4$  in 0.1M PBS at 1.44V.



**Fig. S7.** (A) CV of Pt ultra-microelectrode (UME) in 2mM  $[\text{Fe}(\text{CN})_6]^{3-}$  at  $10\text{mVs}^{-1}$  scan rate and (B) probe approach curve (PAC) of Pt UME in 2mM  $[\text{Fe}(\text{CN})_6]^{3-}$  solution at SBM0 photoanode in dark.

The normalized approach curves are fitted by using these equations 1-6.<sup>15</sup>

$$I_T^{ins}(L, RG) = \frac{\frac{2.08}{RG^{0.358}} \left( L - \frac{0.145}{RG} \right) + 1.585}{\frac{2.08}{RG^{0.358}} (L + 0.0023RG) + 1.57 + \frac{LnRG}{L} + \frac{2}{\pi RG} \ln \left( 1 + \frac{\pi RG}{2L} \right)} \quad (1)$$

$$I_T^{cond}(L + \kappa^{-1}, RG) = \alpha(RG) + \frac{\pi}{4\beta(RG) \arctan(L + \kappa^{-1})} + \left( 1 - \alpha(RG) - \frac{1}{2\beta(RG)} \right)^2 \frac{\pi}{2} \arctan(L + \kappa^{-1}) \quad (2)$$

$$I_T(L, \kappa, RG) = I_T^{cond} \left( L + \frac{1}{\kappa}, RG \right) + \frac{I_T^{ins}(L, RG) - 1}{(1 + 2.47RG^{0.31}L\kappa)(1 + L^{0.006RG + 0.113}\kappa^{-0.023RG + 0.91})} \quad (3)$$

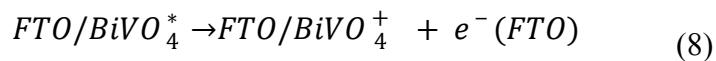
$$I_T = I_s \left( 1 - \frac{I_T^{ins}}{I_T^{cond}} \right) + I_T^{ins} \quad (4)$$

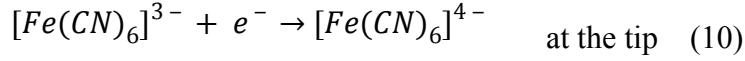
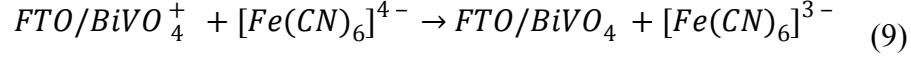
$$\alpha(RG) = \ln 2 + \ln 2 \left( 1 - \frac{2}{\pi} \arccos \left( \frac{1}{RG} \right) \right) - \ln 2 \left( 1 - \left( \frac{2}{\pi} \arccos \left( \frac{1}{RG} \right) \right)^2 \right) \quad (5)$$

$$\beta(RG) = 1 + 0.639 \left( 1 - \frac{2}{\pi} \arccos \left( \frac{1}{RG} \right) \right) - 0.186 \left( 1 - \left( \frac{2}{\pi} \arccos \left( \frac{1}{RG} \right) \right)^2 \right) \quad (6)$$

Where  $RG = r_{\text{glass}} / r_T$  is the ratio of the radius of glass sheath ( $r_{\text{glass}}$ ) to the radius of the active area of Pt UME ( $r_T$ ),  $I_T^{cond}$  is diffusion control current for conducting substrate i.e. positive feedback,  $I_T^{ins}$  is diffusion control current for insulating substrate i.e. negative feedback.

The details reaction mechanism of PEC regeneration has been developed under the steady-state SECM using  $[\text{Fe}(\text{CN})_6]^{4-} / [\text{Fe}(\text{CN})_6]^{3-}$  redox probe on the photoanode<sup>16, 17</sup>.





On solving the above equations using steady-state approximation, the following result has been obtained as

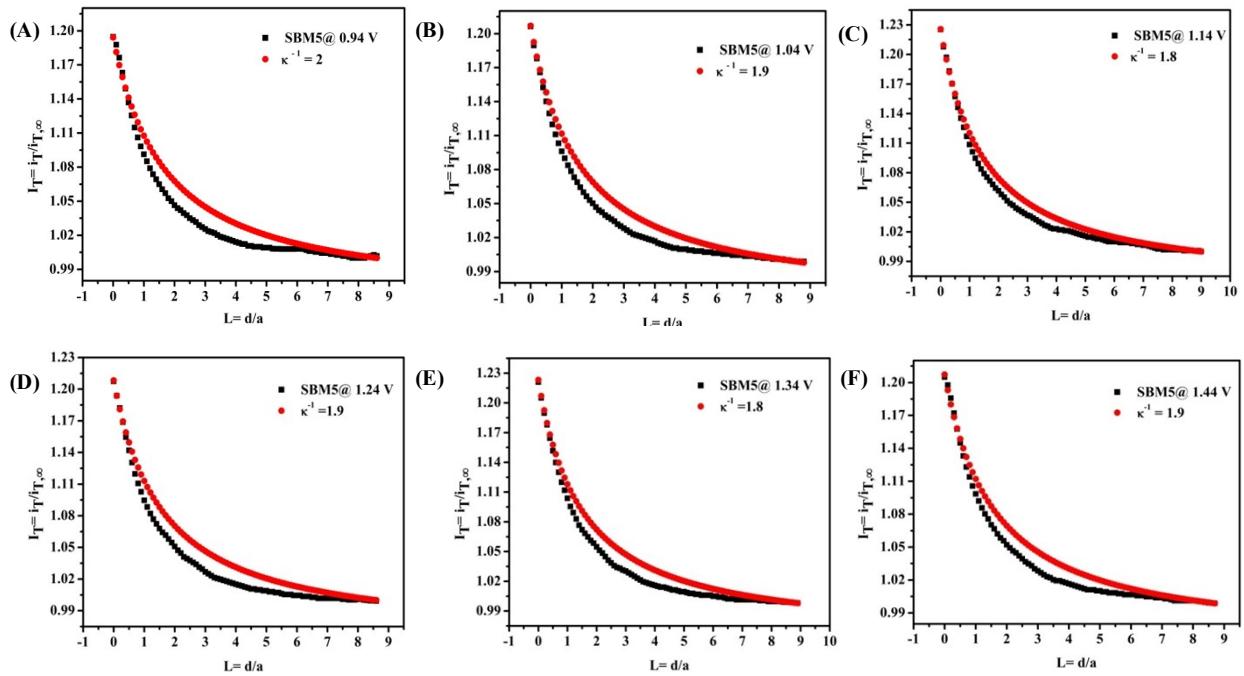
$$\frac{1}{I_s} = \frac{1}{I_{T, \text{cond}}} + \frac{4D_{\text{diffusion}}[Fe^{3+}]^*}{\pi r_T l [BiVO_4^0] \varphi_h J_{hv}} + \frac{4D_{\text{diffusion}}}{\pi r_T l [BiVO_4^0] k_{ox}} \quad (11)$$

For the first-order reaction at the BiVO<sub>4</sub> electrode surface, the following expression is in correlation with the feedback approach curve <sup>18, 19</sup>.

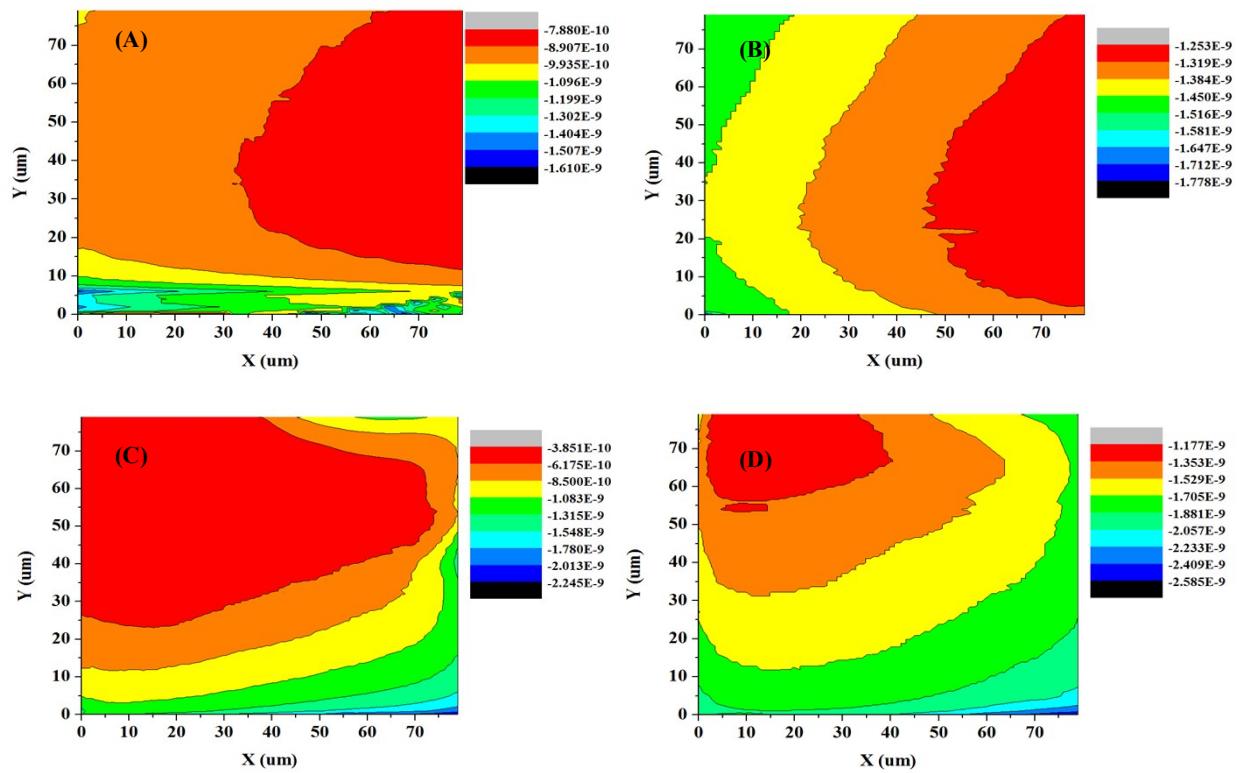
$$\frac{1}{I_s} = \frac{1}{I_{T, \text{cond}}} + \frac{1}{\pi \kappa} \quad (12)$$

$$k_{eff} = \kappa \frac{D_{\text{diffusion}}}{r_T} \quad (13)$$

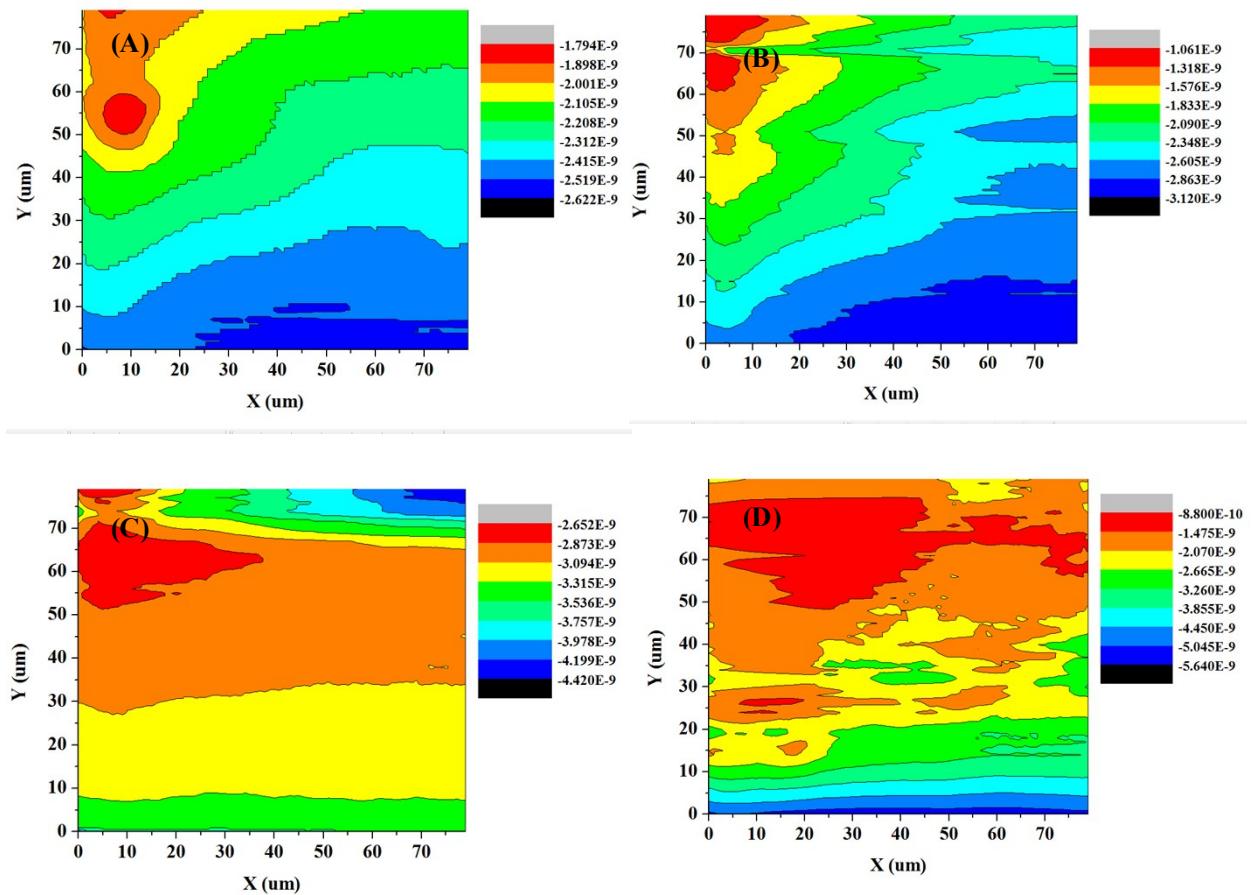
Experimental normalized probe approach curves are fitted using equations 1-6 at different  $\kappa$  and interfacial effective rate constant ( $k_{eff}$ ) is calculated using equation 13. The mapping of BiVO<sub>4</sub> photoanodes was performed by measuring tip current in feedback mode at constant height to quantify the localized surface catalytic activity in PEC.



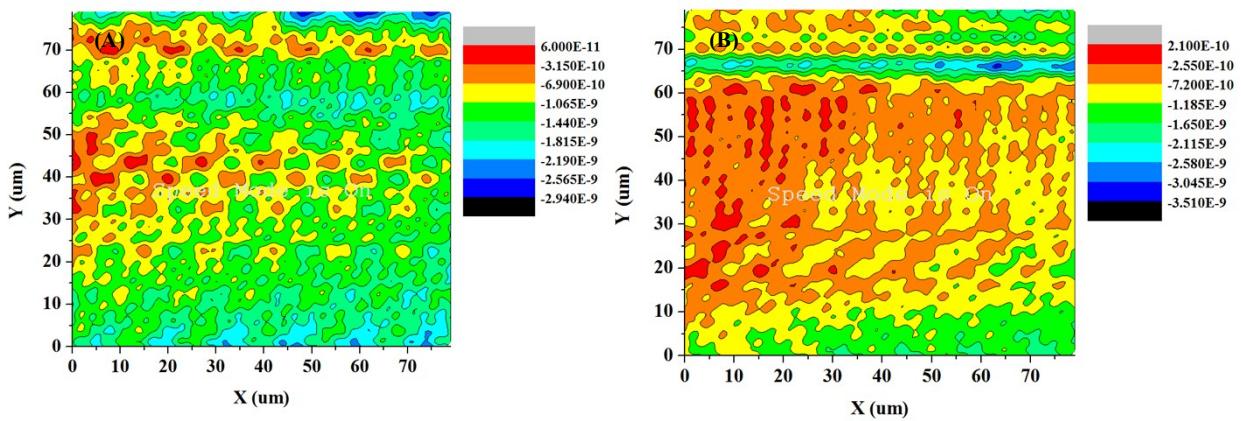
**Fig. S8.** Normalized SECM feedback approach curve of the SBM5 at (A) 0.94V, (B) 1.04V, (C) 1.14V, (D) 1.24V, (E) 1.34V and (F) 1.44V in 2mM  $[\text{Fe}(\text{CN})_6]^{3-}$  solution at different applied potential at substrate under illumination using Pt ultra-microelectrode having  $r_T$  value  $4.8\mu\text{m}$  as calculated from the cyclic voltammetry measurement shown in Supporting Information Fig. S5. The feedback approach curve are fitted with a theoretical model of SECM using equations 8-13 given in the manuscript.



**Fig. S9.** Scanning electrochemical microscopy (SECM) imaging of photoanodes SBM0 at (A) 0.94V and (B) 1.14V and SBM1 at (C) 0.94V and (D) 1.14V substrate potential in 2mM  $[\text{Fe}(\text{CN})_6]^{3-}$  at constant height mode using Pt UME as probe and photoanodes as substrate.



**Fig. S10.** Scanning electrochemical microscopy (SECM) imaging of photoanodes SBM3 at (A) 0.94V and (B) 1.14V and SBM5 at (C) 0.94V and (D) 1.14V substrate potential in 2mM  $[\text{Fe}(\text{CN})_6]^{3-}$  at constant height mode using Pt UME as probe and photoanodes as substrate.



**Fig. S11.** Scanning electrochemical microscopy (SECM) imaging of photoanodes SBM7 at (A) 0.94V and (B) 1.14V substrate potential in 2mM  $[\text{Fe}(\text{CN})_6]^{3-}$  at constant height mode using Pt UME as probe and photoanodes as substrate.

## Reference

1. W. Luo, Z. Yang, Z. Li, J. Zhang, J. Liu, Z. Zhao, Z. Wang, S. Yan, T. Yu and Z. Zou, *Energy & Environmental Science*, 2011, **4**, 4046-4051.
2. S. Pilli, T. Furtak, L. Brown, T. Deutsch, J. Turner and A. Herring, *J. Am. Chem. Soc*, 2011, **133**, 18370-18377.
3. F. F. Abdi, L. Han, A. H. Smets, M. Zeman, B. Dam and R. Van De Krol, *Nature communications*, 2013, **4**, 2195.
4. T. W. Kim and K.-S. Choi, *Science*, 2014, **343**, 990-994.
5. Y. Park, D. Kang and K.-S. Choi, *Physical Chemistry Chemical Physics*, 2014, **16**, 1238-1246.
6. J. H. Kim, Y. Jo, J. H. Kim, J. W. Jang, H. J. Kang, Y. H. Lee, D. S. Kim, Y. Jun and J. S. Lee, *ACS nano*, 2015, **9**, 11820-11829.

7. T. W. Kim, Y. Ping, G. A. Galli and K.-S. Choi, *Nature communications*, 2015, **6**, 8769.
8. M. Zhong, T. Hisatomi, Y. Kuang, J. Zhao, M. Liu, A. Iwase, Q. Jia, H. Nishiyama, T. Minegishi and M. Nakabayashi, *Journal of the American Chemical Society*, 2015, **137**, 5053-5060.
9. M. Rohloff, B. Anke, S. Zhang, U. Gernert, C. Scheu, M. Lerch and A. Fischer, *Sustainable Energy & Fuels*, 2017, **1**, 1830-1846.
10. J.-S. Yang and J.-J. Wu, *Nano Energy*, 2017, **32**, 232-240.
11. M. Huang, J. Bian, W. Xiong, C. Huang and R. Zhang, *Journal of Materials Chemistry A*, 2018, **6**, 3602-3609.
12. S. Byun, G. Jung, S.-Y. Moon, B. Kim, J. Y. Park, S. Jeon, S.-W. Nam and B. Shin, *Nano energy*, 2018, **43**, 244-252.
13. M. Rohloff, B. r. Anke, O. Kasian, S. Zhang, M. Lerch, C. Scheu and A. Fischer, *ACS applied materials & interfaces*, 2019.
14. X. Cao, C. Xu, X. Liang, J. Ma, M. Yue and Y. Ding, *Applied Catalysis B: Environmental*, 2020, **260**, 118136.
15. R. Cornut and C. Lefrou, *Journal of Electroanalytical Chemistry*, 2008, **621**, 178-184.
16. B. Zhang, X. Zhang, X. Xiao and Y. Shen, *ACS applied materials & interfaces*, 2016, **8**, 1606-1614.
17. U. Mengesha Tefashe, K. Nonomura, N. Vlachopoulos, A. Hagfeldt and G. Wittstock, *The Journal of Physical Chemistry C*, 2012, **116**, 4316-4323.
18. C. Wei, A. J. Bard and M. V. Mirkin, *The Journal of Physical Chemistry*, 1995, **99**, 16033-16042.
19. C. Lefrou and R. Cornut, *ChemPhysChem*, 2010, **11**, 547-556.